CLAIMS:

1. A solar cell comprising a monocrystalline silicon substrate having a texture structure at its surface, the monocrystalline silicon substrate including a damaged layer near its surface, the damaged layer originating from a slicing step during the preparation of the substrate,

wherein the damaged layer has a depth of 0.2 to 5 μm.

~~2. The solar cell of claim 1 wherein the damaged layer has a depth of 0.2 to 5 μm.~~

~~3~~2. The solar cell of claim 1, ~~or 2~~ wherein the monocrystalline silicon substrate has a major surface of {100} plane.

~~4~~3. A method of manufacturing a solar cell, comprising the steps of forming a texture on a monocrystalline silicon substrate by chemical etching, said monocrystalline silicon substrate having on its surface a damaged layer originating from a slicing step during the preparation of the substrate, forming a p-n junction, and forming electrodes,

wherein the step of forming a texture is carried out such that the damaged layer originating from a slicing step during the preparation of the substrate is left behind, and the damaged layer having a depth of 0.2 to 5 μm thus remains near the surface of the textured substrate.

~~5. The method of claim 4 wherein the step of forming a texture is carried out such that the damaged layer may have a depth of 0.2 to 5 μm after the texture formation.~~

~~6~~4. The method of claim ~~4 or 5~~3, wherein the monocrystalline silicon substrate has a major surface of {100} plane, and the chemical etching is anisotropic etching using an alkaline aqueous solution so that the texture structure is formed as an arrangement of regular pyramid protrusions delimited by four {111} planes.

~~7~~5. The method of ~~any one of~~ claim~~s~~ 3 or 4, ~~to 6~~ wherein the alkaline aqueous solution used for chemical etching of the surface of the monocrystalline silicon substrate is an aqueous solution containing sodium hydroxide, potassium hydroxide, potassium carbonate, sodium carbonate or sodium hydrogencarbonate.